

METHOD AND SYSTEM TO MEASURE CHARACTERISTICS OF A FILM DISPOSED ON A SUBSTRATE

ABSTRACT OF THE DISCLOSURE

[0041] The present invention is directed to providing a method and system to measure characteristics of a film disposed on a substrate. The method includes identifying a plurality of processing regions on the film; measuring characteristics of a subset of the plurality of processing regions, defining measured characteristics; determining a variation of one of the measured characteristics; and associating a cause of the variations based upon a comparison of the one of the measured characteristics to measured characteristics associated with the remaining processing regions of the subset. The system carries out the aforementioned method.